

Supporting informations :

Microstructure and Oxidation Resistance of Relaxed Epitaxial Nickel Thin Films Grown on (100)- and (110)-SrTiO₃ substrates by Pulsed Laser Deposition

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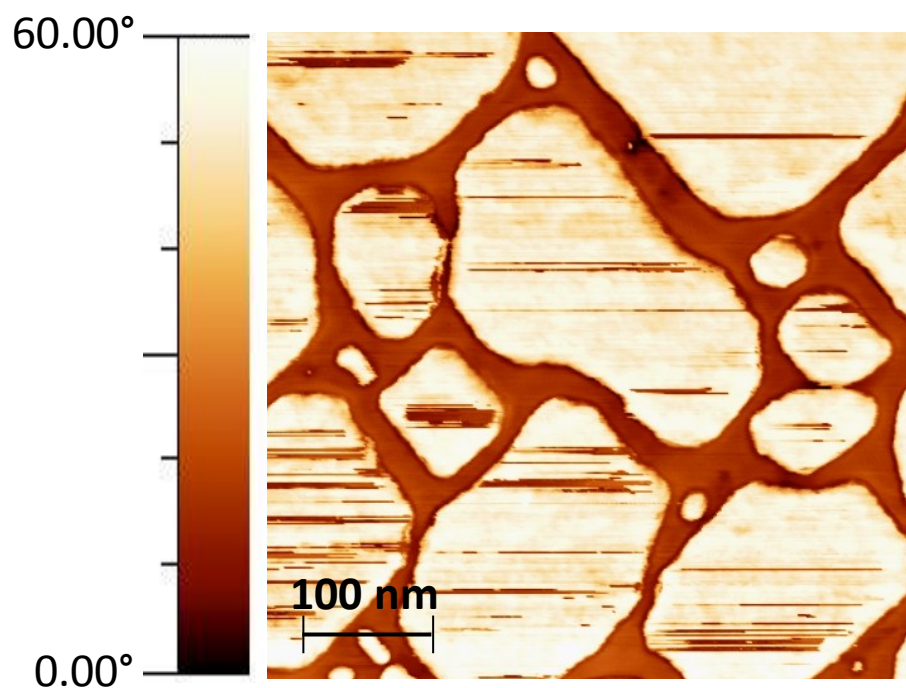


Figure S1. AFM-AC image of the as-deposited Ni thin film on (100)-SrTiO₃